

HW 1 Solution Problem 1-3

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1. Section 3.2: Doped Semiconductors

3.3 For a p -type silicon in which the dopant concentration $N_A = 5 \times 10^{18}/\text{cm}^3$, find the hole and electron concentrations at $T = 300 \text{ K}$.

From Example 3-1 $n_i = 1.5 \times 10^{10}/\text{cm}^3$ at 300 K
(more precise than $10^{10}/\text{cm}^3$ used in the lecture)

$$p \cong N_A = \boxed{5 \times 10^{18}/\text{cm}^3}$$

(100% ionization)

$$np = n_i^2, \quad n = \frac{n_i^2}{p} = \frac{(1.5 \times 10^{10})^2}{5 \times 10^{18}} = \boxed{45/\text{cm}^3} \ll p$$

2. **3.4** For a silicon crystal doped with phosphorus, what must N_D be if at $T = 300 \text{ K}$ the hole concentration drops below the intrinsic level by a factor of 10^8 ?

P (phosphorus) belongs to Group V family of periodic Table \Rightarrow donor \Rightarrow n -type

$$p = \frac{n_i^2}{n} \approx \frac{n_i^2}{N_D}$$

$$\text{Set } p < \frac{n_i}{10^8}$$

$$\frac{n_i^2}{N_D} < \frac{n_i}{10^8}$$

$$N_D > n_i \cdot 10^8$$

$$N_D > 1.5 \times 10^{10} \cdot 10^8$$

$$N_D > \boxed{1.5 \times 10^{18}/\text{cm}^3}$$

3. **3.5** In a phosphorus-doped silicon layer with impurity concentration of $10^{17}/\text{cm}^3$, find the hole and electron concentrations at 27°C and 125°C .

$$n_i = 7.3 \times 10^{15} (300)^{3/2} e^{-1.12/(2 \times 8.62 \times 10^{-5} \times 300)}$$

$$= 1.5 \times 10^{10} \text{ carriers}/\text{cm}^3$$

$n \approx N_D = 10^{17}/\text{cm}^3$ at all temp. above freeze out temp ($\sim 10\text{-}20 \text{ K}$)

$$p = \frac{n_i^2}{n}$$

$$n_i(T) = B \cdot T^{3/2} \cdot e^{-E_g/2kT} \quad \text{--- (1)}$$

$$n_i(300) = B (300)^{3/2} e^{-\frac{E_g}{2k} \left(\frac{1}{300}\right)} \quad \text{--- (2)}$$

$\frac{(1)}{(2)}$:

$$n_i(T) = n_i(300) \cdot \left(\frac{T}{300}\right)^{3/2} \cdot e^{-\frac{E_g}{2k} \left(\frac{1}{T} - \frac{1}{300}\right)}, \quad E_g = 1.12 \text{ eV}, \quad K = 8.62 \times 10^{-5} \text{ eV/K}$$

← Kelvin

↑ Boltzmann's Constant

expressing

$n_i(T)$ using $n_i(300) = 1.5 \times 10^{10}$ as a reference

$$n_i(T) = 1.5 \times 10^{10} \left(\frac{T}{300}\right)^{3/2} e^{-\frac{1.12}{2(8.6 \times 10^{-5})} \left(\frac{1}{T} - \frac{1}{300}\right)}$$

$$\text{at } 27^\circ\text{C} (300\text{K}), \quad \boxed{n = 10^{17}/\text{cm}^3}, \quad p = \frac{(1.5 \times 10^{10})^2}{10^{17}} = \boxed{2.25 \times 10^3/\text{cm}^3}$$

$$\text{at } 125^\circ\text{C} (273 + 125 = 398\text{K}), \quad \boxed{n = 10^{17}/\text{cm}^3}, \quad n_i = 4.8 \times 10^{12}/\text{cm}^3$$

$$p = \frac{n_i^2}{n} = \frac{(4.8 \times 10^{12})^2}{10^{17}} = \boxed{2.3 \times 10^8/\text{cm}^3}$$

Significance of 125°C : This is the around the Max. operating temp of Si IC.